

L Number	Hits	Search Text	DB	Time stamp
-	1330	tungsten adj silicide adj film	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/24 11:34
-	0	(tungsten adj silicide adj film) and "PH.sub.3" and "WF.sub.4" and "SiCl.sub.2 H.sub.2" and "Ar"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/23 14:57
-	1330	(tungsten adj silicide adj film) "WF.sub.4" and "SiCl.sub.2 H.sub.2" and "Ar"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/23 14:57
-	0	(tungsten adj silicide adj film) and "WF.sub.4" and "SiCl.sub.2 H.sub.2" and "Ar"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/23 14:57
-	69	(tungsten adj silicide adj film) and "PH.sub.3"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/23 14:58
-	103	(tungsten adj silicide) near5 phosphorus	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/24 11:35
-	6	(tungsten adj silicide) near5 (phosphorus near3 gas)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/24 11:36
-	736	(tungsten adj silicide) and (polysilicon adj layer) and silicon and (anneal or annealing or annealed) and (oxidizing or oxidation or oxidize)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/24 14:02
-	51	((tungsten adj silicide) and (polysilicon adj layer) and silicon and (anneal or annealing or annealed) and (oxidizing or oxidation or oxidize)) and ((oxidation or oxidizing or oxidize) near5 (sidewall or (side adj wall)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/04/24 16:06